Highly Spin-Polarized Tunneling in Fully Epitaxial Magnetic Tunnel Junctions Using Full-Heusler Alloy Co$_2$Cr$_{0.6}$Fe$_{0.4}$Al Thin Film and MgO Tunnel Barrier


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Highly spin-polarized tunneling with tunnel magnetoresistance (TMR) ratios of 90% at room temperature and 240% at 4.2 K was demonstrated for fully epitaxial magnetic tunnel junctions fabricated using a cobalt-based full-Heusler alloy Co$_2$Cr$_{0.6}$Fe$_{0.4}$Al (CCFA) thin film having a composition close to the stoichiometric one and a MgO tunnel barrier. A high tunneling spin polarization of 0.79 at 4.2 K was obtained for the epitaxial CCFA films from the TMR ratios. This adds to the promise of the fully epitaxial MTJ as a key device structure for utilizing the intrinsically high spin polarizations of Co-based full-Heusler alloy thin films.

Index Terms—Co-based full Heusler alloy, half-metallic ferromagnet, magnetic tunnel junction, tunnel magnetoresistance.

I. INTRODUCTION

INTEREST has been growing in the fabrication of magnetic tunnel junctions (MTJs) with a half-metallic ferromagnet (HMF). An HMF is characterized by an energy gap for the minority-spin band, leading to a complete spin polarization at the Fermi level ($E_F$) [1]. The potentially high spin polarization of HMFs is advantageous for achieving high tunnel magnetoresistance (TMR) ratios in MTJs, efficient spin injection from ferromagnetic electrodes into semiconductors, and current-induced magnetization switching in MTJs. Cobalt-based full-Heusler alloy thin films have been studied intensively because of the half-metallic nature theoretically predicted for some of these alloys [2] and because of their high Curie temperatures [3], [4]. Inomata et al. first demonstrated a relatively high TMR ratio of 16% at room temperature (RT) for MTJs using a Co-based full-Heusler alloy thin film; these MTJs had a polycrystalline Co$_2$Cr$_{0.6}$Fe$_{0.4}$Al (CCFA) thin film as a lower electrode and an amorphous AlO$_x$ tunnel barrier [5]. Recently, relatively high TMR ratios of up to 70% at RT have been shown for MTJs using a Co-based full-Heusler alloy thin film of Co$_2$MnSi and an amorphous AlO$_x$ tunnel barrier [6].

We recently fabricated fully epitaxial MTJs using a Co-based full-Heusler alloy thin film of either Co$_2$Cr$_{0.6}$Fe$_{0.4}$Al (CCFA) or Co$_2$MnGe as a lower electrode and a MgO tunnel barrier [7]–[10] and obtained relatively high TMR ratios of 42% at RT and 74% at 55 K for CCFA/MgO/Co$_2$MnGe MTJs [7]. However, much room remains for further enhancing the TMR ratio by preparing CCFA thin films having a composition close to the stoichiometric one of Co$_2$(Cr$_{0.6}$Fe$_{0.4}$)Al and optimizing the MgO barrier thickness and other fabrication conditions. In this study, we fabricated fully epitaxial MTJs having a CCFA thin film whose composition was close to the stoichiometric one (i.e., the 2:1:1 film composition of Co$_2$(Cr$_{0.6}$Fe$_{0.4}$)Al) and a wedge-shaped MgO tunnel barrier. We then investigated the TMR characteristics of these MTJs.

II. EXPERIMENTAL METHODS

The fabricated epitaxial MTJ layer structure was as follows: (from the substrate side) MgO buffer layer (10 nm)/CCFA lower electrode (50 nm)/MgO tunnel barrier (1.0–3.6 nm)/Co$_2$O$_{39}$Fe$_{20}$ upper electrode (30 nm), grown on a MgO(001) single-crystal substrate. Each layer in the MTJ layer structure was successively deposited in an ultrahigh vacuum chamber through the combined use of magnetron sputtering and electron beam evaporation. The CCFA layer was deposited at RT using magnetron sputtering and subsequently annealed in situ at 500 °C for 15 min. The MgO tunnel barrier was deposited at RT by electron beam evaporation. The Co$_2$O$_{39}$Fe$_{20}$ layer, which had a coercive force higher than that of the CCFA layer, was deposited at RT using magnetron sputtering. The fabrication procedure of the epitaxial MTJ layer structure has been described in detail elsewhere [7]. The composition of the fabricated CCFA film was determined as Co$_2$Cr$_{0.6}$Fe$_{0.4}$Al$_{0.5}$ through inductively coupled plasma analysis with an accuracy of 2%–3% for the composition of each element. Thus, the film composition was certainly brought close to the stoichiometric one of 2:1:1 for Co$_2$(Cr$_{0.6}$Fe$_{0.4}$)Al, and in contrast with that of Co$_2$Cr$_{0.6}$Fe$_{0.4}$Al$_{0.5}$, which was used to fabricate CCFA-MTJ’s showing TMR ratios of about 42% at RT [9]. The nominal thickness of the MgO tunnel barrier ($h_{MgO}$) was varied from 1.0 to 3.6 nm on each 20 × 20 mm substrate by using a linearly moving shifter during the deposition. We fabricated MTJs with the fully epitaxial layer structure through photolithography and Ar ion milling. The fabricated junction sizes were from 4 × 4 μm to 20 × 20 μm. After the microfabrication procedure, the MTJs were annealed at 175 °C for 1 h in a vacuum of 10$^{-4}$ Pa under a magnetic field of 5 kOe. The magnetoresistance was measured with a magnetic field applied along the [110] axis of the CCFA at temperatures from 4.2 K to RT using a dc four-probe method. We defined the TMR ratio as $(R_{AP} - R_{FP})/R_{AP}$, where $R_{AP}$ and $R_{FP}$ are
the respective resistance-area products for the antiparallel
and parallel magnetization configurations between the upper and lower electrodes.

III. EXPERIMENTAL RESULTS AND DISCUSSION

We investigated the structural properties of the fabricated CCFA films and MTJ layer structures. First, we confirmed that the fabricated CCFA films were epitaxial and crystallized in the B2 structure by X-ray pole figure measurements, which was in agreement with our previous work [7]–[9]. Microbeam electron diffraction patterns with beam diameters of 10–30 nm also indicated the fabricated CCFA layer had the B2 structure. Fig. 1 shows a cross-sectional high-resolution transmission electron microscope lattice image of a CCFA (50 nm)/MgO (2 nm)/Co80Fe20 (30 nm) MTJ layer structure along the [110] direction of the CCFA film. This image clearly shows that all the layers of the CCFA/MgO/Co80Fe20 MTJ layer structure were grown epitaxially and were single-crystalline [Fig. 1(b)]. It also confirmed that extremely smooth and abrupt interfaces were formed.

The as-fabricated (i.e., not ex situ annealed) MTJs exhibited typical TMR ratios of 80% at RT and 210% at 4.2 K. The significant increase of the TMR ratio in the epitaxial CCFA-MTJs compared with our previously reported value of about 42% at RT [7] indicates that a film composition close to the stoichiometric one is essential to obtain high spin polarizations in CCFA thin films. Fig. 2 shows RAp and TMR ratios of as-fabricated MTJs at RT as a function of thMgO. As can be seen, a clear exponential dependence of RAp on thMgO was observed for a range of thMgO from 1.1 to 2.8 nm, indicating typical tunnel junction behavior. The mtΦ0 value estimated from the slope of the ln(RAp) versus thMgO according to the Wenzel–Kramer–Brillouin (WK) approximation was 0.32 eV for the CCFA-MTJ, where mt is the effective electron mass normalized by the bare electron mass and Φ0 is the potential barrier height (the energy difference between the Fermi level of the emitter ferromagnetic electrode and the bottom of the conduction band in the tunnel barrier). This value was close to that of 0.39 eV for epitaxial Fe/MgO/Fe MTJs [11]. High TMR ratios from 50% to 83% were obtained at RT for a wide range of thMgO from 1.1 to 2.8 nm. Note that no significant dependence of the TMR ratio on thMgO over this wide range was similar to that observed for epitaxial Fe/MgO/Fe MTJs [11] and MTJs with a highly oriented MgO tunnel barrier and Co1−xFe2x electrode films [12].

Fig. 3(a) shows typical magnetoresistance curves at V = 5 mV at RT and 4.2 K for an MTJ postfabrication annealed at 175 °C with a 1.6-nm-thick MgO tunnel barrier. Typical TMR ratios of 90% at RT and 240% at 4.2 K were obtained for the MTJ’s postfabrication annealed at 175 °C.

One notable feature of the TMR characteristics is the strong temperature (T) dependence of the TMR ratio. Fig. 3(b) shows the TMR ratio and RAp at a bias voltage of 5 mV as a function of T from 4.2 K to RT for an MTJ postfabrication annealed at 175 °C. With decreasing T from RT to 4.2 K, the TMR ratio increased 2.7 times from the value of 90% at RT to that of 240% at 4.2 K. As shown in Fig. 3(b), RAp also increased with decreasing T, while RAp was almost independent of T. These results indicate that the increase in the TMR ratio with decreasing T was mainly due to the RAp increases. To clarify the physical origin of the observed marked temperature dependence of the TMR ratio of the fully epitaxial CCFA/MgO/CoFe MTJs, further detailed and systematic studies are needed.

We estimated the spin polarization for the CCFA electrodes by using Jullière’s model for the TMR ratio; i.e., TMR ratio = 2P1P2/(1 – P1P2), where P1 and P2 are the spin polarizations at EF of the ferromagnetic electrodes in MTJs [13]. Thus, the spin polarization estimated using Jullière’s model for fully epitaxial, single-crystal MTJs, such as those used in this study, should be regarded as an effective spin polarization, or a tunneling spin polarization. As a reference sample for the estimation, we also fabricated fully epitaxial exchange-biased Co50Fe50/MgO/Co50Fe50 MTJs (Co50Fe50-MTJs). The layer
structure was (from the substrate side) Co$_2$Fe$_2$Al (50 nm)/MgO (0.8–3.4 nm)/Co$_2$Fe$_2$O$_{10}$ (3 nm)/Ru (0.8 nm)/Co$_2$Fe$_{0.4}$Al (2 nm)/IrMn (10 nm)/Ru (5 nm), grown on a MgO-buffered MgO substrate. The microfabricated Co$_2$Fe$_2$O$_{10}$-MTJs showed typical TMR ratios of 90% at RT and 240% at 4.2 K. Using these obtained TMR ratios with Jullièr’s model resulted in an effective spin polarization for the Co$_2$Fe$_2$O$_{10}$ film ($P_{\text{CoFe}}$) of 0.69 at 4.2 K (0.62 at RT). If we estimate the effective spin polarization of the CCFA film ($P_{\text{CCFA}}$) from the TMR ratio of 240% at 4.2 K (90% at RT) by using Jullièr’s model with the $P_{\text{CoFe}}$ of 0.69 at 4.2 K (0.62 at RT), we obtain a $P_{\text{CCFA}}$ value of 0.79 at 4.2 K (0.50 at RT). This $P_{\text{CCFA}}$ value (0.79 at 4.2 K) was close to the value of 0.78 theoretically predicted through the band structure calculation for CCFA with the B2 structure [14]. The obtained high spin polarization supports the promise of fully epitaxial MTJ layer structures as a key device structure for utilizing the intrinsically high spin polarization of Co-based full-Heusler alloy thin films.

IV. SUMMARY

Highly spin-polarized tunneling was demonstrated for fully epitaxial magnetic tunnel junctions (MTJs) fabricated using a cobalt-based full-Heusler alloy Co$_2$Cr$_{1-x}$Fe$_x$Al (CCFA) thin film whose composition was close to the stoichiometric one and a MgO tunnel barrier. The microfabricated MTJs exhibited high tunnel magnetoresistance ratios of 90% at RT and 240% at 4.2 K. A high effective spin polarization of 0.79 at 4.2 K was obtained for the epitaxial CCFA films.

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REFERENCES

[8] ———, “High tunnel magnetoresistance in epitaxial Co$_2$Cr$_{0.8}$Fe$_{0.2}$ Al/MgO/CoFe tunnel junctions,” IEEE Trans. Magn., vol. 41, pp. 2603–2605, 2005.